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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/930,787
Filing Date August 14, 2001
Inventor Luan C. Tran et al.
Assignee Micron Technology, Inc.
Group Art Unit 2814
Examiner Howard Weiss
Attorney's Docket No. MI22-1784
Title: Memory Integrated Circuitry

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT


References -See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 9-15-03


By: 
D. Brent Kenady
Reg. No. 40,045

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Form PTO-1449 		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1784		SERIAL NO. 09/930,787		
STATE OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Luan Tran et al.				
				FILING DATE August 14, 2001		GROUP 2814		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,736,670	4/7/1998	Carbonell et al.				
	AB	6,297,129 B2	10/02/01	Tran et al.				
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Fazan et al., "A Highly Manufacturable Trench Isolation Process for Deep Submicron DRAMs," ©1993 IEEE, 4 pages.					
	AS							
	AT							
EXAMINER				DATE CONSIDERED				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								